

U.S. Department of Commerce, Patent and Trademark Office (PTO Form 1449 modified)		Docket No. AMAT/2592.C6/DSM /LOW K JW	Serial No. 10/632,179
INFORMATION DISCLOSURE STATEMENT BY APPLICANT		Applicant Xia, et al.	Confirmation No. Unknown
(Use several sheets if necessary)		Filing Date July 31, 2003	Group Unknown
Examiner Unknown			

## U.S. Patent Documents

*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate
B2	A1	6,570,256	05/27/2003	Conti, et al.	257	761	07/20/2001
	A2	6,524,972	02/25/2003	Maeda	438	778	03/09/2000
	A3	6,475,564	11/05/2002	Carter, et al.	427	249.15	07/06/2000
	A4	6,242,366	06/05/2001	Beekman, et al.	438	790	02/17/1999
	A5	6,211,096	04/03/2001	Sandhu, et al.	438	725	12/22/1998
	A6	6,169,021	01/02/2001	Akram, et al.	438	612	12/18/1998
	A7	6,159,871	12/12/2000	Loboda, et al.	438	786	05/29/1998
	A8	6,147,009	11/14/2000	Grill, et al.	438	780	06/29/1998
	A9	6,140,226	10/31/2000	Grill, et al.	438	637	07/30/1998
	A10	6,072,227	06/06/2000	Yau, et al.	257	642	07/13/1998
	A11	6,068,884	05/30/2000	Rose, et al.	427	255.6	04/28/1998
	A12	6,054,379	04/25/2000	Yau, et al.	438	623	02/11/1998
	A13	6,054,206	04/25/2000	Mountsier	428	312.8	06/22/1998

## Foreign Patent Documents

*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
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B2	B1	59 98726	06/07/1984	JP	BOIJ	12/00	<input checked="" type="checkbox"/>	<input type="checkbox"/>
	B2	6-163521	06/10/1994	JP (Abstract)	HOIL	21/314	<input checked="" type="checkbox"/>	<input type="checkbox"/>
	B3	6-168937	06/14/1994	JP (Abstract)	HOIL	21/316	<input checked="" type="checkbox"/>	<input type="checkbox"/>
	B4	8-222559	08/30/1996	JP (Abstract)	HOIL	21/316	<input checked="" type="checkbox"/>	<input type="checkbox"/>
	B5	8-236518	09/13/1996	JP (Abstract)	HOIL	21/316	<input checked="" type="checkbox"/>	<input type="checkbox"/>
	B6	8-288286	11/01/1996	JP (Abstract)	HOIL	21/316	<input checked="" type="checkbox"/>	<input type="checkbox"/>
	B7	9-008031	01/10/1997	JP	HOIL	21/316	<input type="checkbox"/>	<input checked="" type="checkbox"/>
	B8	05267480	10/15/1993	JP (Abstract)	HOIL	21/90	<input checked="" type="checkbox"/>	<input type="checkbox"/>

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## U.S. Patent Documents

*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate
Dr	A14	5,989,998	11/23/1999	Sugahara, et al.	438	623	08/28/1997
	A15	5,891,799	04/06/1999	Tsui	438	624	08/18/1997
	A16	5,888,593	03/30/1999	Petrmichl, et al.	427	563	04/12/1996
	A17	5,858,880	01/12/1999	Dobson, et al.	438	758	01/05/1996
	A18	5,834,162	11/10/1998	Malba	430	317	10/28/1996
	A19	5,821,168	10/13/1998	Jain	438	692	07/16/1997
	A20	5,818,071	10/06/1998	Loboda, et al.	257	77	02/02/1995
	A21	5,817,572	10/06/1998	Chiang, et al.	438	624	12/18/1996
	A22	5,807,785	09/15/1998	Ravi	438	624	08/02/1996
	A23	5,789,319	08/04/1998	Havemann, et al.	438	668	02/26/1996
	A24	5,753,564	05/19/1998	Fukada	438	624	06/07/1995
Dr	A25	5,739,579	04/14/1998	Chiang, et al.	257	635	09/10/1996

## Foreign Patent Documents

*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
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Dr	B9	92/12535	07/23/1992	JP	HOIL	21/312	<input type="checkbox"/>	<input checked="" type="checkbox"/>
	B10	01050429	02/27/1989	JP (Abstract Only)	H01L	21/318	<input checked="" type="checkbox"/>	<input type="checkbox"/>
	B11	60111480	06/17/1985	JP			<input type="checkbox"/>	<input checked="" type="checkbox"/>
	B12	9-237785	09/09/1997	JP	HOIL	21/316	<input type="checkbox"/>	<input checked="" type="checkbox"/>
Dr	B13	0 774 533 A1	05/21/1997	EP	C23C	16/40	<input type="checkbox"/>	<input checked="" type="checkbox"/>
	B14	0 519 079 A1	12/09/1991	EP	HOIL	21/312	<input type="checkbox"/>	<input checked="" type="checkbox"/>

## OTHER ART

*Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.
Dr	C1	C.D. Dobson, A. Kiermasz, K. Beekman, R.J. Wilby, "Advanced SiO <sub>2</sub> Planarization Using Silane and H <sub>2</sub> O <sub>2</sub> ," December 1994, pages 85-87

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## U.S. Patent Documents

*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate
✓	A26	5,703,404	12/30/1997	Matsuura	257	758	12/24/1996
	A27	5,700,720	12/23/1997	Hashimoto	438	622	12/20/1995
	A28	5,693,563	12/02/1997	Teong	437	190	07/15/1996
	A29	5,683,940	11/04/1997	Yashiro	438	760	12/20/1995
	A30	5,679,413	10/21/1997	Petrmichle, et al.	427	534	10/11/1996
	A31	5,638,251	06/10/1997	Goel, et al.	361	313	10/03/1995
	A32	5,637,351	06/10/1997	O'Neal, et al.	427	255.37	05/11/1995
	A33	5,618,619	04/08/1997	Petrmichl, et al.	428	334	03/03/1994
	A34	5,616,369	04/01/1997	Williams, et al.	427	560	06/24/1994
	A35	5,598,027	01/28/1997	Matsuura	257	635	12/21/1995
	A36	5,593,741	01/14/1997	Ikeda	427	579	06/28/1995
	A37	5,578,523	11/26/1996	Fiordalice, et al.	438	633	05/18/1995
✓	A38	5,563,105	10/08/1996	Dobuzinsky, et al.	437	240	09/30/1994

## Foreign Patent Documents

*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
							YES	NO
✓	B15	0 469 926 A1	02/05/1992	EP	C08J	7/06	<input type="checkbox"/>	<input checked="" type="checkbox"/>
	B16	0 522 799 A2	01/13/1993	EP	H01L	21/90	<input type="checkbox"/>	<input checked="" type="checkbox"/>
	B17	0 721 019 A2	07/10/1996	EP	H01L	16/40	<input type="checkbox"/>	<input checked="" type="checkbox"/>
	B18	0 721 019 A3	07/02/1997	EP	H01L	21/316	<input type="checkbox"/>	<input checked="" type="checkbox"/>
	B19	0 711 817 A2	05/15/1996	EP	C09D	183/04	<input type="checkbox"/>	<input checked="" type="checkbox"/>
	B20	0 885 983 A1	12/23/1998	EP	C23C	16/30	<input type="checkbox"/>	<input checked="" type="checkbox"/>
✓	B21	0 743 675 A1	11/20/1996	EP	H01L	21/312	<input type="checkbox"/>	<input checked="" type="checkbox"/>

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Dr	A39	5,559,367	09/24/1996	Cohen, et al.	157	77	07/12/1994
	A40	5,554,570	09/10/1996	Maeda, et al.	437	235	01/09/1995
	A41	5,508,368	04/16/1996	Knapp, et al.	427	534	03/03/1994
	A42	5,494,712	02/27/1996	Hu, et al.	427	489	11/17/1994
	A43	5,492,736	02/20/1996	Laxman, et al.	427	579	11/28/1994
	A44	5,488,015	01/30/1996	Havemann, et al.	437	195	05/20/1994
	A45	5,468,520	11/21/1995	Williams, et al.	427	560	06/24/1994
	A46	5,466,431	11/14/1995	Dorfman, et al.	423	446	05/25/1994
	A47	5,465,680	11/14/1995	Loboda	117	84	07/01/1993
	A48	5,364,666	11/15/1994	Williams, et al.	427	579	09/23/1993
	A49	5,362,526	11/08/1994	Wang, et al.	427	573	01/23/1991
	A50	5,360,646	11/01/1994	Morita	427	574	09/01/1993
	A51	5,352,493	10/04/1994	Dorfman, et al.	427	530	05/03/1991
Dr	A52	5,314,724	05/24/1994	Tsukune, et al.	427	489	12/19/1991

## Foreign Patent Documents

*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
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Dr	B22	0 960 958 A2	05/27/1999	EP	C23C	16/30	<input type="checkbox"/>	<input checked="" type="checkbox"/>
	B23	0 849 789 A2	06/24/1998	EP	H01L	21/311	<input type="checkbox"/>	<input checked="" type="checkbox"/>
	B24	0 840 365 A2	05/06/1998	EP	H01L	21/311	<input type="checkbox"/>	<input checked="" type="checkbox"/>
	B25	196 54 737 A1	07/03/1997	GERMANY	HOIL	21/31	<input checked="" type="checkbox"/>	<input type="checkbox"/>
Dr	B26	198 04 375 A1	01/07/1999	GERMANY	HOIL	21/312	<input type="checkbox"/>	<input checked="" type="checkbox"/>

## OTHER ART

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Examiner Dr Date Considered 2/21/04

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Dr	A53	5,298,587	03/29/1994	Hu, et al.	528	10	12/21/1992
	A54	5,290,736	03/01/1994	Sato, et al.	438	761	09/24/1991
	A55	5,279,867	01/18/1994	Friedt, et al.	427	583.2	07/09/1992
	A56	5,250,473	10/05/1993	Smits	438	790	08/02/1991
	A57	5,246,887	09/21/1993	Yu	438	761	07/10/1991
	A58	5,224,441	07/06/1993	Felts, et al.	118	718	09/27/1991
	A59	5,204,141	04/20/1993	Roberts, et al.	427	255.3	09/18/1991
	A60	5,124,014	06/23/1992	Foo, et al.	204	92.32	04/11/1991
	A61	5,120,680	06/09/1992	Foo, et al.	438	789	07/19/1990
	A62	5,093,153	03/03/1992	Brochot, et al.	427	41	02/07/1989
	A63	5,040,046	08/13/1991	Chabra, et al.	357	54	10/09/1990
Dr	A64	5,028,566	07/02/1991	Lagendijk	438	784	07/27/1990

## F reign Patent Documents

*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
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Dr	B27	98/59089	12/30/1998	WO	C23C	16/30	<input type="checkbox"/>	<input checked="" type="checkbox"/>
	B28	00/01012	01/06/2000	WO	H01L	23/48	<input type="checkbox"/>	<input checked="" type="checkbox"/>
	B29	98/08249	02/26/1998	WO	H01L	21/312	<input type="checkbox"/>	<input checked="" type="checkbox"/>
	B30	99/38202	07/29/1999	WO	H01L	21/312	<input type="checkbox"/>	<input checked="" type="checkbox"/>
	B31	99/41423	08/19/1999	WO	C23C		<input type="checkbox"/>	<input checked="" type="checkbox"/>
Dr	B32	94/01885	01/20/1994	WO	H01L	21/316	<input type="checkbox"/>	<input checked="" type="checkbox"/>

## OTHER ART

*Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.
	C3	M. Matsuura, et al. "Novel Self-Planarizing CVD Oxide for Interlayer Dielectric Applications," 1994, pages 5.7.1.-5.7.4

Examiner Dr Date Considered 2/21/04

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## U.S. Patent Documents

*Examiner Initial		Document Number	Issue Date	Applicant(s) Name	Class	Subclass	Filing Date If Appropriate
<i>DL</i>	A65	4,981,724	01/01/1991	Hochberg, et al.	427	255.3	10/27/1988
	A66	4,973,511	11/27/1990	Farmer, et al.	428	216	12/01/1998
	A67	4,900,591	02/13/1990	Bennett, et al.	427	255	01/20/1988
	A68	4,894,352	01/16/1990	Lane, et al.	437	238	10/26/1988
	A69	4,845,054	07/04/1989	Mitchener	437	238	06/29/1987
	A70	4,828,880	05/09/1989	Jenkins, et al.	427	167	12/21/1987
	A71	4,824,690	04/25/1989	Heinecke, et al.	427	38	11/03/1987
	A72	4,812,325	03/14/1989	Ishihara, et al.	427	69	10/21/1986
	A73	4,798,629	01/17/1989	Wood, et al.	106	287.16	10/22/1987
	A74	4,789,648	12/06/1988	Chow, et al.	438	633	10/28/1985
	A75	4,557,946	12/10/1985	Sacher, et al.	427	41	06/03/1983
	A76	4,532,150	07/30/1985	Endo, et al.	427	577	12/22/1983
	A77	4,168,330	09/18/1979	Kaganowicz	427	39	10/13/1977
	A78	2003/0032306	12/13/2003	Conti, et al.	438	778	08/10/2001
<i>DL</i>	A79	2002/0105084	08/08/2002	Li	257	759	12/27/2001

## Foreign Patent Documents

*Examiner Initial		Document Number	Date	Country	Class	Subclass	Translation	
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	B35						<input type="checkbox"/>	<input type="checkbox"/>
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\*Examiner Initial      Including Author, Title, Date, Pertinent Pages, Etc.

Examiner

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<b>OTHER ART</b>			
*Examiner Initial		Including Author, Title, Date, Pertinent Pages, Etc.	
DL	C4	Frederic Gaillard, et al., "Silicon Dioxide Chemical Vapor Deposition Using Silane and Hydrogen Peroxide," J. Vac. Sci. Technol. Jul/Aug 1996, pages 2767-2769	
	C5	N. Inagaki et al., "Plasma Polymerization Of Organosilicon Compounds", Journal of Applied Polymer Science, Vol. 30, pp. 3385-3395 (1985)	
	C6	A. Nara, et al. "Low Dielectric Constant Insulator Formed by Downstream Plasma CVD at Room Temperature Using TMS/O <sub>2</sub> ", Japanese Journal of Applied Physics, Vol. 36. No. 3B (March 1997)	
	C7	A. Grill, et al. "Low Dielectric Constant Films Prepared by Plasma-Enhanced Chemical Vapor Deposition From Tetramethylsilane", Journal of Applied Physics, Vol. 85. No. 6 (March 1999)	
	C8	Luther et al., "Planar Copper-Polyimide Back End Of The Line Interconnections For ULSI Devices", June 8-9 1993, VMIC Conference, 1993 ISMIC-102/93/0015, pp. 15-21,	
	C9	Y. Osada et al., "Plasma-Exposed Polymerization Of Cyclic Organosiloxanes In The Condensed Phase", Journal of Polymer Science: Polymer Letters Edition, Vol. 19, pp. 369-374 (1981)	
	C10	P. Favia et al., "The Role Of Substrate Temperature And Bias In The Plasma Deposition From Tetramethylsilane", Plasma Sources Sci. Technol. 1 (1992) pp. 59-66	
	C11	D.S. Kim et al., "Deposition Of Thermally Stable, Low Dielectric Constant Fluorocarbon/SiO <sub>2</sub> Composite Thin Film", American Institute Of Physics, Appl. Phys. Lett., Vol. 69, No. 18, Oct. 28, 1996, pp. 2776-2778	
	C12	V. Hazari et al., Characterization Of Alternative Chemistries For Depositing PECVD Silicon Dioxide Films, DUMIC Conference,--333D/98/0319, pp. 319-326, Feb. 1998	
	C13	R. McCabe et al., "Large Area Diamond-Like Carbon Coatings By Ion Implantation", Surface Engineering Vol. III: Process Technology and Surface Analysis, pp. 163-172, 1995	
	C14	K.H.A. Bogart, et al. "Plasma Enhanced Chemical Vapor Deposition of SiO <sub>2</sub> Using Novel Alkoxysilane Precursors" Journal of Vacuum Science & Technology A 13(2) Mar/Apr 1995.	
	C15	P. Favia, "Plasma Deposition Of Thin Films From a Fluorine-Containing Cyclosiloxane", Journal Of Polymer Science: Part A: Polymer Chemistry, 1992, 10 pp.	
DL	C16	Y. Segui et al., "In Situ Electrical Property Measurements Of Metal (Plasma Polysiloxane)/Metal Structures", Thin Solid Films, 155 (1987) pp. 175-185, Electronics and Optics	
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<i>PL</i>	C17	Y. Segui et al., "Gas Discharge In Hexamethyldisiloxane", Journal of Applied Polymer Science, Vol. 20 pp. 1611-1618 (1976)	
	C18	N. Inagaki et al., "Preparation Of Siloxane-Like Films By Glow Discharge Polymerization", Journal of Applied Polymer Science, Vol. 29, pp. 3595-3605 (1984)	
	C19	V.S. Nguyen et al., " Plasma Organosilicon Polymers", J. Electrochem. Soc. Solid-State Science and Technology, Vol. 132, No. 8, pp. 1925-1932, Aug. 1985	
	C20	K. J. Taylor et al., "Parylene Copolymers", Spring MRS, Symposium N, pp. 1-9, 1997	
	C21	S. McClatchie, et al., "Low Dielectric Constant Flowfill Technology For IMD Applications" DUMIC Conference 1997 ISMIC-222D/97/0034 (February 10-11, 1997)	
	C22	C. Rau et al, "Mechanisms Of Plasma Polymerization Of Various Silico-Organic Monomers", Thin Solid Films, pp. 28-37, 249 (1994)	
	C23	S. Sahli et al., "Properties Of Plasma-Polysiloxane Deposited By PECVD", Materials Chemistry and Physics, pp. 106-109, 33 (1993)	
	C24	A.M. Wrobel et al., "Oligomeric Products In Plasma-Polymerized Organosilicones", J. Macromol. Sci-Chem., A20 (5&6), pp. 583-618 (1983)	
	C25	M. R. Wertheimer et al., "Advances In Basic And Applied Aspects Of Microwave Plasma Polymerization", Thin Solid Films, 115 (1984) pp. 109-124	
	C26	J.A. Theil et al., "Carbon Content Of Silicon Oxide Films Deposited By Room Temperature Plasma Enhanced Chemical Vapor Deposition Of Hexamethyldisiloxane And Oxygen", Journal of Vacuum Science Technology, A 12(4), Jul./Aug. 1994, pp. 1365-1370	
	C27	European Search Report Dated October 26, 2000	
	C28	European Search Report for EP 00 11 2300, Dated August 24, 2001	
	C29	Laura Peters, "Pursuing the Perfect Low K Dielectrics" Semiconductor International, September 1998	
<i>PL</i>	C30	Bin Zhao, et al. "Integration of Low Dielectrics Constant Materials in Advanced Aluminum & Copper Interconnects", Materials Research Symposium Proc., Vol. 564, Materials Research Society, 1999. Pages 485-497	
		<i>2/21/04</i>	
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